제25회 한국반도체학술대회

 The 25th Korean Conference on Semiconductors

 2018년 2월 5일(월)-7일(수), 강원도 하이원리조트 컨벤션 호텔

2018년 2월 7일(수), 09:00-10:30 Room C (함백I, 5층)

D. Thin Film Process Technology 분과

[WC1-D] ALD/CVD Process (2D Materials)

좌장: 민요셉 교수(건국대학교), 한정환 교수(서울과학기술대학교)

WC1-D-1 09:00-09:15Synthesis of 2-D SnS Thin Films and Their Potential Applications In-Hwan Baek ^{1,2} , Jung Joon Pyeon ^{1,3} , Taek-Mo Chung ⁴ , Jeong Hwan Han ⁵ , Cheol Seong Hwang ² , and Seong Keun Kim ¹ ¹ Center for Electronic Materials, KIST, ² Department of Materials Science and Engineering, and Inter-University Semiconductor Research Center, Seoul National University, ³ KU-KIST Graduate School of Converging Science and Technology, ⁴ Division of Advanced Materials, KRICT, ⁵ Department of Materials Science and Engineering, Seoul National University of Science and TechnologyWC1-D-2 09:15-09:30Characterizations of Charge-Trap Memory Thin-Film Transistors with HfO2 Charge-Trap Layer Controlled by Atomic Layer Deposition Process So-Yeong Na and Sung-Min Yoon Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee UniversityWC1-D-3 09:30-09:45Synthesis of 2-Dimensional Single Phase SnS ₂ by Atomic Layer Deposition Jung Joon Pyeon ^{1,2} , In-Hwan Baek ^{1,3} , Taek-Mo Chung ⁴ , Jeong Hwan Han ⁵ , Chong- Yun Kang ^{1,2} , Seong Keun Kim ¹ ¹ Center for Electronic Materials, KIST, ² KU-KIST Graduate School of Converging Science and Technology, Korea University ³ Department of Materials Science and Engineering, and Inter-university Semiconductor Research Center, Seoul National University, ⁴ Division of Advanced Materials, KIRICT, ⁵ Department of Materials Science and Engineering, Seoul National University of Science and TechnologyWC1-D-4 09:45-10:00Continuous and Ultrathin ALD Ru Film Deposition Using Discrete Feeding Method (DFM) and Electric Field Assisted ALD (EA-ALD) Hyun Soo Jin and Tae Joo Park Department of Materials Science and Chemical Engineering, Hanyang University	WC1-D-1In-Hwan Baek ^{1,2} , Jung Joon Pyeon ^{1,3} , Taek-Mo Chung ⁴ , Jeong Hwan Han ⁵ , Cheol Seong Hwang ² , and Seong Keun Kim ¹ ''Center for Electronic Materials, KIST, ² Department of Materials Science and Engineering, and Inter-University Semiconductor Research Center, Seoul National University, ³ KU-KIST Graduate School of Converging Science and Technology, ⁴ Division of Advanced Materials, KRICT, ⁵ Department of Materials Science and Engineering, Seoul National University of Science and TechnologyWC1-D-2 09:15-09:30Characterizations of Charge-Trap Memory Thin-Film Transistors with HfO2 Charge-Trap Layer Controlled by Atomic Layer Deposition Process So-Yeong Na and Sung-Min Yoon Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee UniversityWC1-D-3 09:30-09:45Synthesis of 2-Dimensional Single Phase SnS2by Atomic Layer Deposition Jung Joon Pyeon ^{1,2} , In-Hwan Baek ^{1,3} , Taek-Mo Chung ⁴ , Jeong Hwan Han ⁵ , Chong- Yun Kang ^{1,2} , Seong Keun Kim ¹ 'Center for Electronic Materials, KIST, ² KU-KIST Graduate School of Converging Science and Technology, Korea University, ³ Department of Materials Science and Engineering, and Inter-University Semiconductor Research Center, Seoul National University, ⁴ Division of Advanced Materials, KIRCT, ⁵ Department of Materials Science and Technology, Korea University, Science and TechnologyWC1-D-4 09:45-10:00Continuous and Ultrathin ALD Ru Film Deposition Using Discrete Feeding Method (DFM) and Electric Field Assisted ALD (EA-ALD) Hyun Soo Jin and Tae Joo Park Department of Materials Science and Chemical Engineering, Hanyang UniversityWill Be Cubic BeO Thin Films the Next-Generation Dielectric? Seong Keun Kim ¹ , Woo Chul Lee ¹ , Eric S, Larsen ^{2,3} , Jung Hwan Yum ^{2,3} , and
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